SYSTEM AND METHOD FOR ETCHING
RESIN WITH AN OZONE WET ETCHING PROCESS

ABSTRACT OF THE INVENTION

5   A method is provided for cleaning resin residue in liquid crystal display (LCD) or integrated circuit (IC) fabrication process. The method comprises: forming an electrode layer; forming an interlayer film of resin overlying the electrode later; patterning the resin interlayer; forming a via to access the first area of the electrode

10   layer; in response to forming the via, forming a resin residue overlying a first area of the electrode layer; introducing a gas mixture including ozone into water to create a moist ozone gas, where the gas mixture is approximately 10 % ozone by molecular weight (wt %); wet ashing the resin residue overlying the first area of the electrode layer using the

15   moist ozone gas; and, depositing a metal layer overlying the first area of the electrode to form a pixel electrode.